

Kazunori Koga

List of Publications by Year in descending order

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254
papers

3,383
citations

159358

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h-index

223531

46
g-index

256
all docs

256
docs citations

256
times ranked

2023
citing authors

#	ARTICLE	IF	CITATIONS
1	Plasma Agriculture from Laboratory to Farm: A Review. <i>Processes</i> , 2020, 8, 1002.	1.3	125
2	Extension of the operational regime of the LHD towards a deuterium experiment. <i>Nuclear Fusion</i> , 2017, 57, 102023.	1.6	116
3	Review of pulmonary toxicity of indium compounds to animals and humans. <i>Thin Solid Films</i> , 2010, 518, 2934-2936.	0.8	95
4	Plasma induced long-term growth enhancement of <i>Raphanus sativus</i> L. using combinatorial atmospheric air dielectric barrier discharge plasmas. <i>Current Applied Physics</i> , 2014, 14, S149-S153.	1.1	85
5	Effects of Gas Temperature Gradient, Pulse Discharge Modulation, and Hydrogen Dilution on Particle Growth in Silane RF Discharges. <i>Japanese Journal of Applied Physics</i> , 2000, 39, 287-293.	0.8	84
6	Simple method of improving harvest by nonthermal air plasma irradiation of seeds of <i>Arabidopsis thaliana</i> (L.). <i>Applied Physics Express</i> , 2016, 9, 016201.	1.1	83
7	In situ observation of nucleation and subsequent growth of clusters in silane radio frequency discharges. <i>Applied Physics Letters</i> , 2000, 77, 196-198.	1.5	77
8	Influence of ionic liquid and ionic salt on protein against the reactive species generated using dielectric barrier discharge plasma. <i>Scientific Reports</i> , 2015, 5, 17781.	1.6	70
9	Effects of plasma irradiation using various feeding gases on growth of <i>Raphanus sativus</i> L.. <i>Archives of Biochemistry and Biophysics</i> , 2016, 605, 129-140.	1.4	64
10	Highly Conducting and Very Thin ZnO:Al Films with ZnO Buffer Layer Fabricated by Solid Phase Crystallization from Amorphous Phase. <i>Applied Physics Express</i> , 2011, 4, 011101.	1.1	61
11	Growth Enhancement of Radish Sprouts Induced by Low Pressure O_2 Radio Frequency Discharge Plasma Irradiation. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 01AE01.	0.8	58
12	Highly Stable a-Si:H Films Deposited by Using Multi-Hollow Plasma Chemical Vapor Deposition. <i>Japanese Journal of Applied Physics</i> , 2005, 44, L1430-L1432.	0.8	57
13	Effects of nonthermal plasma jet irradiation on the selective production of H_2O_2 and NO_2^{\bullet} in liquid water. <i>Journal of Applied Physics</i> , 2016, 120, .	1.1	52
14	Single step method to deposit Si quantum dot films using H_2+SiH_4 VHF discharges and electron mobility in a Si quantum dot solar cell. <i>Surface and Coatings Technology</i> , 2007, 201, 5468-5471.	2.2	50
15	Impact of Gamma rays and DBD plasma treatments on wastewater treatment. <i>Scientific Reports</i> , 2018, 8, 2926.	1.6	49
16	Fabrication of Nanoparticle Composite Porous Films Having Ultralow Dielectric Constant. <i>Japanese Journal of Applied Physics</i> , 2005, 44, L1509-L1511.	0.8	48
17	Growth Control of Dry Yeast Using Scalable Atmospheric-Pressure Dielectric Barrier Discharge Plasma Irradiation. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 11PJ02.	0.8	47
18	Cluster-Suppressed Plasma Chemical Vapor Deposition Method for High Quality Hydrogenated Amorphous Silicon Films. <i>Japanese Journal of Applied Physics</i> , 2002, 41, L168-L170.	0.8	46

#	ARTICLE	IF	CITATIONS
19	Correlation between volume fraction of clusters incorporated into a-Si:H films and hydrogen content associated with Si-H bonds in the films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2004, 22, 1536-1539.	0.9	42
20	Two-dimensional concentration distribution of reactive oxygen species transported through a tissue phantom by atmospheric-pressure plasma-jet irradiation. <i>Applied Physics Express</i> , 2016, 9, 076202.	1.1	41
21	Nano-factories in plasma: present status and outlook. <i>Journal Physics D: Applied Physics</i> , 2011, 44, 174038.	1.3	40
22	Effects of gas flow on oxidation reaction in liquid induced by He/O ₂ plasma-jet irradiation. <i>Journal of Applied Physics</i> , 2015, 118, .	1.1	39
23	Plant Growth Enhancement of Seeds Immersed in Plasma Activated Water. <i>MRS Advances</i> , 2017, 2, 995-1000.	0.5	38
24	In situ simple method for measuring size and density of nanoparticles in reactive plasmas. <i>Journal of Applied Physics</i> , 2006, 99, 083302.	1.1	36
25	Effects of irradiation distance on supply of reactive oxygen species to the bottom of a Petri dish filled with liquid by an atmospheric O ₂ /He plasma jet. <i>Journal of Applied Physics</i> , 2016, 119, .	1.1	36
26	High rate deposition of highly stable a-Si:H films using multi-hollow discharges for thin films solar cells. <i>Surface and Coatings Technology</i> , 2010, 205, S241-S245.	2.2	35
27	Extension of operation regimes and investigation of three-dimensional currentless plasmas in the Large Helical Device. <i>Nuclear Fusion</i> , 2013, 53, 104015.	1.6	35
28	Transport of nano-particles in capacitively coupled rf discharges without and with amplitude modulation of discharge voltage. <i>Journal Physics D: Applied Physics</i> , 2007, 40, 2267-2271.	1.3	32
29	Growth Enhancement of Radish Sprouts Induced by Low Pressure O ₂ Radio Frequency Discharge Plasma Irradiation. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 01AE01.	0.8	32
30	Polymer counter electrode of poly(3,4-ethylenedioxythiophene):Poly(4-styrenesulfonate) containing TiO ₂ nano-particles for dye-sensitized solar cells. <i>Journal of Power Sources</i> , 2016, 307, 25-30.	4.0	32
31	Alterations of DNA Methylation Caused by Cold Plasma Treatment Restore Delayed Germination of Heat-Stressed Rice (<i>Oryza sativa</i> L.) Seeds. <i>ACS Agricultural Science and Technology</i> , 2021, 1, 5-10.	1.0	32
32	Analysis on the effect of polysulfide electrolyte composition for higher performance of Si quantum dot-sensitized solar cells. <i>Electrochimica Acta</i> , 2013, 95, 43-47.	2.6	31
33	Visualization of the Distribution of Oxidizing Substances in an Atmospheric Pressure Plasma Jet. <i>IEEE Transactions on Plasma Science</i> , 2014, 42, 2482-2483.	0.6	30
34	Relationship between cold plasma treatment-induced changes in radish seed germination and phytohormone balance. <i>Japanese Journal of Applied Physics</i> , 2020, 59, SH1001.	0.8	30
35	Production of crystalline Si nano-clusters using pulsed H ₂ +SiH ₄ VHF discharges. <i>Thin Solid Films</i> , 2006, 506-507, 288-291.	0.8	29
36	High quality epitaxial ZnO films grown on solid-phase crystallized buffer layers. <i>Thin Solid Films</i> , 2012, 520, 4674-4677.	0.8	28

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37	Dielectric barrier discharge plasma treatment-induced changes in sunflower seed germination, phytohormone balance, and seedling growth. <i>Applied Physics Express</i> , 2019, 12, 126003.	1.1	28
38	Impact of seed color and storage time on the radish seed germination and sprout growth in plasma agriculture. <i>Scientific Reports</i> , 2021, 11, 2539.	1.6	28
39	Characterization of Dust Particles Ranging in Size from 1 nm to 10 μm Collected in the LHD. <i>Plasma and Fusion Research</i> , 2009, 4, 034-034.	0.3	26
40	Surface nitridation of silicon nano-particles using double multi-chollow discharge plasma CVD. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 3017-3020.	0.8	26
41	Rapid transport of nano-particles having a fractional elementary charge on average in capacitively-coupled rf discharges by amplitude-modulating discharge voltage. <i>Faraday Discussions</i> , 2008, 137, 127-138.	1.6	25
42	Progress and perspectives in dry processes for nanoscale feature fabrication: fine pattern transfer and high-aspect-ratio feature formation. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0802.	0.8	24
43	Impact of atmospheric pressure plasma treated seeds on germination, morphology, gene expression and biochemical responses. <i>Japanese Journal of Applied Physics</i> , 2021, 60, 040502.	0.8	24
44	Nucleation and subsequent growth of clusters in reactive plasmas. <i>Plasma Sources Science and Technology</i> , 2002, 11, A229-A233.	1.3	23
45	Formation Kinetics and Control of Dust Particles in Capacitively-Coupled Reactive Plasmas. <i>Physica Scripta</i> , 2001, T89, 29.	1.2	21
46	Cluster-eliminating filter for depositing cluster-free a-Si:H films by plasma chemical vapor deposition. <i>Review of Scientific Instruments</i> , 2005, 76, 113501.	0.6	21
47	Impacts of Amplitude Modulation of RF Discharge Voltage on the Growth of Nanoparticles in Reactive Plasmas. <i>Applied Physics Express</i> , 2011, 4, 105001.	1.1	21
48	Growth of single crystalline films on lattice-mismatched substrates through 3D to 2D mode transition. <i>Scientific Reports</i> , 2020, 10, 4669.	1.6	21
49	H-assisted plasma CVD of Cu films for interconnects in ultra-large-scale integration. <i>Science and Technology of Advanced Materials</i> , 2001, 2, 505-515.	2.8	20
50	Cluster-suppressed plasma CVD for deposition of high quality a-Si:H films. <i>Thin Solid Films</i> , 2003, 427, 1-5.	0.8	20
51	Mechanism of Cu deposition from Cu(EDMDD) ₂ using H-assisted plasma CVD. <i>Thin Solid Films</i> , 2006, 506-507, 197-201.	0.8	20
52	Cold Plasma Treatment of Sunflower Seeds Modulates Plant-Associated Microbiome and Stimulates Root and Lateral Organ Growth. <i>Frontiers in Plant Science</i> , 2020, 11, 568924.	1.7	20
53	Impact of radish sprouts seeds coat color on the electron paramagnetic resonance signals after plasma treatment. <i>Japanese Journal of Applied Physics</i> , 2020, 59, SHHF01.	0.8	20
54	The protective action of osmolytes on the deleterious effects of gamma rays and atmospheric pressure plasma on protein conformational changes. <i>Scientific Reports</i> , 2017, 7, 8698.	1.6	19

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55	Impact of an ionic liquid on protein thermodynamics in the presence of cold atmospheric plasma and gamma rays. <i>Physical Chemistry Chemical Physics</i> , 2017, 19, 25277-25288.	1.3	19
56	Nanoparticle coagulation in fractionally charged and charge fluctuating dusty plasmas. <i>Physics of Plasmas</i> , 2008, 15, .	0.7	18
57	The reduction of charge recombination and performance enhancement by the surface modification of Si quantum dot-sensitized solar cell. <i>Electrochimica Acta</i> , 2013, 87, 213-217.	2.6	18
58	Effect of Nitridation of Si Nanoparticles on the Performance of Quantum-Dot Sensitized Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 01AD01.	0.8	18
59	Temperature and Pressure Dependences of the Gr ^{1/4} neisen Constant of a Mat of Polyethylene Single Crystals. <i>Polymer Journal</i> , 1975, 7, 14-20.	1.3	17
60	Species responsible for Si-H ₂ bond formation in a-Si:H films deposited using silane high frequency discharges. <i>Thin Solid Films</i> , 2006, 506-507, 17-21.	0.8	17
61	Local supply of reactive oxygen species into a tissue model by atmospheric-pressure plasma-jet exposure. <i>Journal of Applied Physics</i> , 2019, 125, 213303.	1.1	17
62	Control of deposition profile of Cu for large-scale integration (LSI) interconnects by plasma chemical vapor deposition. <i>Pure and Applied Chemistry</i> , 2005, 77, 391-398.	0.9	16
63	Transport control of dust particles via the electrical asymmetry effect: experiment, simulation and modelling. <i>Journal Physics D: Applied Physics</i> , 2013, 46, 245202.	1.3	16
64	Epitaxial Growth of ZnInON Films with Tunable Band Gap from 1.7 to 3.3 eV on ZnO Templates. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 11NM06.	0.8	16
65	Fabrication of ZnInON/ZnO multi-quantum well solar cells. <i>Thin Solid Films</i> , 2015, 587, 106-111.	0.8	15
66	Effects of Nitrogen on Crystal Growth of Sputter-Deposited ZnO Films for Transparent Conducting Oxide. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 11NB03.	0.8	14
67	Size and flux of carbon nanoparticles synthesized by Ar+CH ₄ multi-hollow plasma chemical vapor deposition. <i>Diamond and Related Materials</i> , 2020, 109, 108050.	1.8	14
68	Clustering phenomena in low-pressure reactive plasmas. Basis and applications. <i>Pure and Applied Chemistry</i> , 2002, 74, 483-487.	0.9	13
69	Carbon Particle Formation Due to Interaction Between H ₂ Plasma and Carbon Fiber Composite Wall. <i>IEEE Transactions on Plasma Science</i> , 2004, 32, 405-409.	0.6	13
70	Subacute Pulmonary Toxicity of Copper Indium Gallium Diselenide Following Intratracheal Instillations into the Lungs of Rats. <i>Journal of Occupational Health</i> , 2012, 54, 187-195.	1.0	13
71	Growth Control of Dry Yeast Using Scalable Atmospheric-Pressure Dielectric Barrier Discharge Plasma Irradiation. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 11PJ02.	0.8	13
72	Gas Flow Rate Dependence of the Discharge Characteristics of a Plasma Jet Impinging Onto the Liquid Surface. <i>IEEE Transactions on Plasma Science</i> , 2015, 43, 4081-4087.	0.6	13

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73	Effect of sulfur doped TiO ₂ on photovoltaic properties of dye-sensitized solar cells. <i>Electronic Materials Letters</i> , 2016, 12, 530-536.	1.0	13
74	Cold plasma treatment of <i>Arabidopsis thaliana</i> (L.) seeds modulates plant-associated microbiome composition. <i>Applied Physics Express</i> , 2020, 13, 076001.	1.1	13
75	Influence of osmolytes and ionic liquids on the Bacteriorhodopsin structure in the absence and presence of oxidative stress: A combined experimental and computational study. <i>International Journal of Biological Macromolecules</i> , 2020, 148, 657-665.	3.6	13
76	Possible impact of plasma oxidation on the structure of the C-terminal domain of SARS-CoV-2 spike protein: a computational study. <i>Applied Physics Express</i> , 2021, 14, 027002.	1.1	13
77	Functional nitrogen science based on plasma processing: quantum devices, photocatalysts and activation of plant defense and immune systems. <i>Japanese Journal of Applied Physics</i> , 2022, 61, SA0805.	0.8	13
78	Piezoelectric properties of oriented films of poly(L-methyl D-glutamate). <i>Journal of Polymer Science, Polymer Physics Edition</i> , 1976, 14, 401-414.	1.0	12
79	Behavior of the Ion Sheath Instability in a Negative Ion Plasma. <i>Japanese Journal of Applied Physics</i> , 1999, 38, 1553-1557.	0.8	12
80	Discharge power dependence of H [±] intensity and electron density of Ar+H ₂ discharges in H-assisted plasma CVD reactor. <i>Surface and Coatings Technology</i> , 2008, 202, 5659-5662.	2.2	12
81	Two-Dimensional Spatial Profile of Volume Fraction of Nanoparticles Incorporated Into a-Si:H Films Deposited by Plasma CVD. <i>IEEE Transactions on Plasma Science</i> , 2008, 36, 888-889.	0.6	12
82	Redox Characteristics of Thiol Compounds Using Radicals Produced by Water Vapor Radio Frequency Discharge. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 08JF04.	0.8	12
83	In situ analysis of size distribution of nano-particles in reactive plasmas using two dimensional laser light scattering method. <i>Journal of Instrumentation</i> , 2012, 7, C04017-C04017.	0.5	12
84	High Amount Cluster Incorporation in Initial Si Film Deposition by SiH ₄ Plasma Chemical Vapor Deposition. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 01AD01.	0.8	12
85	Improvement of Si Adhesion and Reduction of Electron Recombination for Si Quantum Dot-Sensitized Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 01AD05.	0.8	12
86	Surface Modification of Polymer Counter Electrode for Low Cost Dye-sensitized Solar Cells. <i>Electrochimica Acta</i> , 2016, 210, 880-887.	2.6	12
87	Outcomes of Pulsed Electric Fields and Nonthermal Plasma Treatments on Seed Germination and Protein Functions. <i>Agronomy</i> , 2022, 12, 482.	1.3	12
88	Anisotropic deposition of Cu in trenches by H-assisted plasma chemical vapor deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2004, 22, 1903-1907.	0.9	11
89	Quantum dot-sensitized solar cells using Si nanoparticles. <i>Transactions of the Materials Research Society of Japan</i> , 2010, 35, 597-599.	0.2	11
90	Improvement on the Electron Transfer of Dye-Sensitized Solar Cell Using Vanadium Doped TiO ₂ . <i>Japanese Journal of Applied Physics</i> , 2013, 52, 11NM02.	0.8	11

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91	Densities and Surface Reaction Probabilities of Oxygen and Nitrogen Atoms During Sputter Deposition of ZnInON on ZnO. IEEE Transactions on Plasma Science, 2017, 45, 323-327.	0.6	11
92	Progress in photovoltaic performance of organic/inorganic hybrid solar cell based on optimal resistive Si and solvent modified poly(3,4-ethylenedioxythiophene) poly(styrenesulfonate) junction. Progress in Photovoltaics: Research and Applications, 2018, 26, 145-150.	4.4	11
93	Long-term response of Norway spruce to seed treatment with cold plasma: Dependence of the effects on the genotype. Plasma Processes and Polymers, 2021, 18, 2000159.	1.6	11
94	Treatment of organic wastewater by a combination of non-thermal plasma and catalyst: a review. Reviews of Modern Plasma Physics, 2022, 6, .	2.2	11
95	Anisotropic deposition of copper by H-assisted plasma chemical vapor deposition. Materials Science in Semiconductor Processing, 2002, 5, 301-304.	1.9	10
96	Characteristics of photocurrent generation in the near-ultraviolet region in Si quantum-dot sensitized solar cells. Thin Solid Films, 2013, 544, 93-98.	0.8	10
97	Dust particle formation due to interaction between graphite and helicon deuterium plasmas. Fusion Engineering and Design, 2013, 88, 28-32.	1.0	10
98	Off-axis sputter deposition of ZnO films on c-sapphire substrates by utilizing nitrogen-mediated crystallization method. Optical Engineering, 2014, 53, 087109.	0.5	10
99	Effects of cluster incorporation into hydrogenated amorphous silicon films in initial discharge phase on film stability. Thin Solid Films, 2015, 587, 126-131.	0.8	10
100	Redox Characteristics of Thiol Compounds Using Radicals Produced by Water Vapor Radio Frequency Discharge. Japanese Journal of Applied Physics, 2011, 50, 08JF04.	0.8	10
101	Mass density control of carbon films deposited by H-assisted plasma CVD method. Surface and Coatings Technology, 2013, 228, S15-S18.	2.2	9
102	Effects of Hydrogen Dilution on ZnO Thin Films Fabricated via Nitrogen-Mediated Crystallization. Japanese Journal of Applied Physics, 2013, 52, 01AC08.	0.8	9
103	Theory for correlation between plasma fluctuation and fluctuation of nanoparticle growth in reactive plasmas. Japanese Journal of Applied Physics, 2014, 53, 010201.	0.8	9
104	Room Temperature Fabrication of (ZnO) _x (InN) _{1-x} films with Step-Terrace Structure by RF Magnetron Sputtering. MRS Advances, 2016, 1, 115-119.	0.5	9
105	Plant Growth Response to Atmospheric Air Plasma Treatments of Seeds of 5 Plant Species. MRS Advances, 2016, 1, 1265-1269.	0.5	9
106	Green route for ammonium nitrate synthesis: fertilizer for plant growth enhancement. RSC Advances, 2021, 11, 28521-28529.	1.7	9
107	Effects of deposition rate and ion bombardment on properties of a-C:H films deposited by H-assisted plasma CVD method. Japanese Journal of Applied Physics, 2016, 55, 01AA11.	0.8	9
108	Propagation Characteristics of Ion Acoustic Waves in an Ar/SF ₆ Plasma. Journal of the Physical Society of Japan, 2000, 69, 1925-1926.	0.7	8

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109	Control of radial density profile of nano-particles produced in reactive plasma by amplitude modulation of radio frequency discharge voltage. <i>Thin Solid Films</i> , 2012, 523, 76-79.	0.8	8
110	Correlation between SiH_2/SiH and light-induced degradation of $\text{p}^+\text{i}^-\text{n}$ hydrogenated amorphous silicon solar cells. <i>Japanese Journal of Applied Physics</i> , 2016, 55, 07LE03.	0.8	8
111	Blue Photoluminescence of $(\text{ZnO})_{0.92}(\text{InN})_{0.08}$. <i>MRS Advances</i> , 2017, 2, 277-282.	0.5	8
112	Real-time monitoring of surface passivation of crystalline silicon during growth of amorphous and epitaxial silicon layer. <i>Journal of Applied Physics</i> , 2020, 128, 033302.	1.1	8
113	Experimental identification of the reactive oxygen species transported into a liquid by plasma irradiation. <i>Japanese Journal of Applied Physics</i> , 2020, 59, 110502.	0.8	8
114	Deposition Profile Control of Carbon Films on Patterned Substrates using a Hydrogen-assisted Plasma CVD Method. <i>Materials Research Society Symposia Proceedings</i> , 2009, 1222, 1.	0.1	7
115	Hybrid sensitized solar cells using Si nanoparticles and ruthenium dye. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 3021-3024.	0.8	7
116	Effect of Nitridation of Si Nanoparticles on the Performance of Quantum-Dot Sensitized Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2012, 51, 01AD01.	0.8	7
117	In-situ Measurements of Cluster Volume Fraction in Silicon Thin Films Using Quartz Crystal Microbalances. <i>Materials Research Society Symposia Proceedings</i> , 2012, 1426, 307-311.	0.1	7
118	Study on the Fabrication of Paint-Type Si Quantum Dot-Sensitized Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 10MB07.	0.8	7
119	SiC Nanoparticle Composite Anode for Li-Ion Batteries. <i>Materials Research Society Symposia Proceedings</i> , 2014, 1678, 7.	0.1	7
120	Electrochemical impedance analysis on the additional layers for the enhancement on the performance of dye-sensitized solar cell. <i>Thin Solid Films</i> , 2014, 554, 122-126.	0.8	7
121	Multigeneration Effects of Plasma Irradiation to Seeds of <i>Arabidopsis Thaliana</i> and <i>Zinnia</i> on Their Growth. <i>Materials Research Society Symposia Proceedings</i> , 2015, 1723, 7.	0.1	7
122	Progress and perspectives in dry processes for leading-edge manufacturing of devices: toward intelligent processes and virtual product development. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SE0804.	0.8	7
123	Graphene-Si ₃ N ₄ nanocomposite blended polymer counter electrode for low-cost dye-sensitized solar cells. <i>Chemical Physics Letters</i> , 2020, 758, 137920.	1.2	7
124	Effects of surrounding gas on plasma-induced downward liquid flow. <i>Japanese Journal of Applied Physics</i> , 2020, 59, SHHF02.	0.8	7
125	Effect of gas flow rate and discharge volume on CO_2 methanation with plasma catalysis. <i>Japanese Journal of Applied Physics</i> , 2022, 61, SI1002.	0.8	7
126	Observation of Local Structures in Asymmetric Ion Sheath. <i>Journal of the Physical Society of Japan</i> , 1999, 68, 1578-1584.	0.7	6

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127	Temperature Dependence of Dielectric Constant of Nanoparticle Composite Porous Low-k Films Fabricated by Pulse Radio Frequency Discharge with Amplitude Modulation. Japanese Journal of Applied Physics, 2008, 47, 6875-6878.	0.8	6
128	P-type sp ³ -bonded BN/n-type Si heterodiode solar cell fabricated by laser-plasma synchronous CVD method. Journal Physics D: Applied Physics, 2009, 42, 225107.	1.3	6
129	The improvement on the performance of quantum dot-sensitized solar cells with functionalized Si. Thin Solid Films, 2013, 546, 284-288.	0.8	6
130	Hysteresis in volume fraction of clusters incorporated into a-Si:H films deposited by SiH ₄ plasma chemical vapor deposition. Surface and Coatings Technology, 2017, 326, 388-394.	2.2	6
131	Transportation of reactive oxygen species in a tissue phantom after plasma irradiation. Japanese Journal of Applied Physics, 2018, 57, 01AG01.	0.8	6
132	Controlling feeding gas temperature of plasma jet with Peltier device for experiments with fission yeast. Japanese Journal of Applied Physics, 2019, 58, SEEG03.	0.8	6
133	Highly efficient and transparent counter electrode for application in bifacial solar cells. Chemical Physics Letters, 2021, 768, 138369.	1.2	6
134	A device for trapping nano-particles formed in processing plasmas for reduction of nano-waste. Surface and Coatings Technology, 2007, 201, 5701-5704.	2.2	5
135	Comparison between silicon thin films with and without incorporating crystalline silicon nanoparticles into the film. Thin Solid Films, 2011, 519, 6896-6898.	0.8	5
136	Effects of Atmospheric Pressure Dielectric Barrier Discharge Plasma Irradiation on Yeast Growth. Materials Research Society Symposia Proceedings, 2012, 1469, 86.	0.1	5
137	Effects of crystalline nanoparticle incorporation on growth, structure, and properties of microcrystalline silicon films deposited by plasma chemical vapor deposition. Thin Solid Films, 2012, 523, 29-33.	0.8	5
138	Discharge power dependence of carbon dust flux in a divertor simulator. Journal of Nuclear Materials, 2013, 438, S788-S791.	1.3	5
139	Effects of DC substrate bias voltage on dust flux in the Large Helical Device. Journal of Nuclear Materials, 2013, 438, S727-S730.	1.3	5
140	Analysis on the photovoltaic property of Si quantum dot-sensitized solar cells. International Journal of Precision Engineering and Manufacturing, 2014, 15, 339-343.	1.1	5
141	Fluctuation of Position and Energy of a Fine Particle in Plasma Nanofabrication. Materials Science Forum, 2016, 879, 1772-1777.	0.3	5
142	Effects of gas flow rate on deposition rate and number of Si clusters incorporated into a-Si:H films. Japanese Journal of Applied Physics, 2016, 55, 01AA19.	0.8	5
143	Low temperature rapid formation of Au-induced crystalline Ge films using sputtering deposition. Thin Solid Films, 2017, 641, 59-64.	0.8	5
144	Comparison between Ar+CH ₄ cathode and anode coupling chemical vapor depositions of hydrogenated amorphous carbon films. Thin Solid Films, 2021, 729, 138701.	0.8	5

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145	Impact of Reactive Oxygen and Nitrogen Species Produced by Plasma on Mdm2â€“p53 Complex. International Journal of Molecular Sciences, 2021, 22, 9585.	1.8	5
146	Effects of concentrated light on the performance and stability of a quasi-solid electrolyte in dye-sensitized solar cells. Chemical Physics Letters, 2021, 781, 138986.	1.2	5
147	Low-Pressure Methanation of CO ₂ Using a Plasmaâ€“Catalyst System. Science of Advanced Materials, 2018, 10, 1087-1090.	0.1	5
148	Effects of Gas Velocity on Deposition Rate and Amount of Cluster Incorporation into a-Si:H Films Fabricated by SiH ₄ & Plasma Chemical Vapor Deposition. Plasma and Fusion Research, 2018, 13, 1406082-1406082.	0.3	5
149	Time of Flight Size Control of Carbon Nanoparticles Using Ar+CH ₄ Multi-Hollow Discharge Plasma Chemical Vapor Deposition Method. Processes, 2021, 9, 2.	1.3	5
150	Influence of Atmospheric Pressure Torch Plasma Irradiation on Plant Growth. Materials Research Society Symposia Proceedings, 2012, 1469, 92.	0.1	4
151	Rapid Growth of Radish Sprouts Using Low Pressure O ₂ Radio Frequency Plasma Irradiation. Materials Research Society Symposia Proceedings, 2012, 1469, 61.	0.1	4
152	Correlation between Volume Fraction of Silicon Clusters in Amorphous Silicon Films and Optical Emission Properties of Si [*] and SiH [*] . Japanese Journal of Applied Physics, 2013, 52, 11NA07.	0.8	4
153	Performance dependence of Si quantum dot-sensitized solar cells on counter electrode. Japanese Journal of Applied Physics, 2014, 53, 05FZ01.	0.8	4
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